

Amendments to the Specification:

Please replace paragraph 24 with the following amended paragraph:

[0024]           The photolithographic apparatus 100 shown in FIGS. 3A and 3B further includes a light source 12 that directs light 13 through a condenser 14 and onto the reticles ~~118, 119~~140, 150, and a lens system 20 that focuses the light being transmitted through the reticles ~~118, 119~~140, 150 onto the photoreactive layer 26 formed on a wafer 24. The wafer 24 is supported on a moveable stage 30. Those skilled in the art will appreciate that the term "light," as used herein, may mean any form of electromagnetic radiation, whether from the visible, infrared, or ultraviolet portions of the spectrum.